

SPECIFICATION AMENDMENTS

Please amend the paragraph 0029 as follows:

0029 FIG. 3 illustrates a block diagram 60 of a laser generator and detection system, in accordance with a preferred embodiment of the present invention. FIG. 3 thus depicts a wafer 68 which may be utilized during the course of a semiconductor fabrication operation, such as, for example, a wafer spin-coating operation. One or more laser light sources are also indicated in FIG. 3. Such laser light sources are laser generator 62 and laser detector 64 ~~65~~, along with laser generator 82 and laser detector 84. Arrow 72 indicates normal photoresist (PR) dust flow, while arrow 80 indicates abnormal PR dust flow.